

Ultrafast High Voltage Kicker System Hardware for Ion Clearing Gaps

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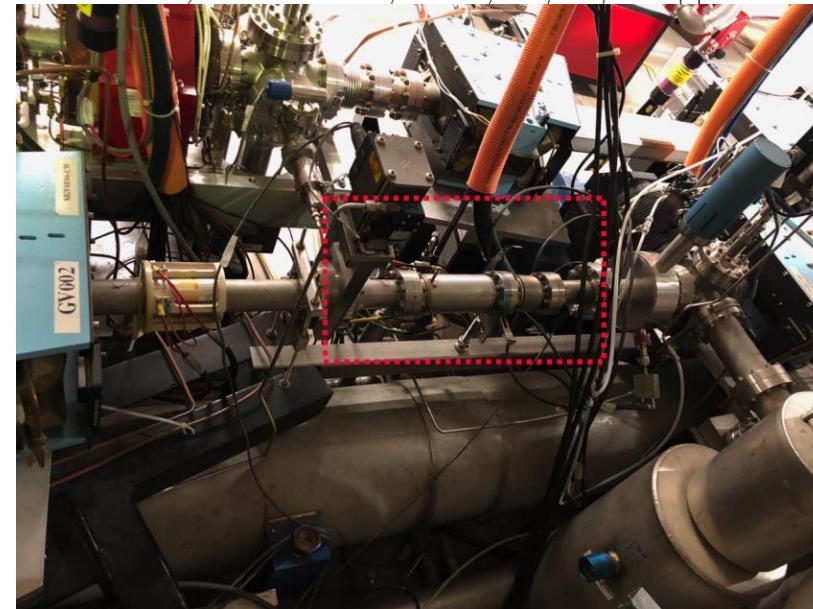
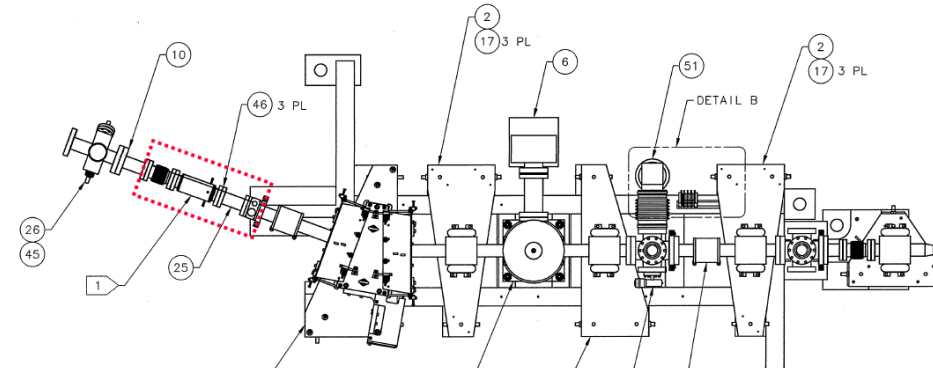
Presenter: Alexander Smirnov, Ph.D.

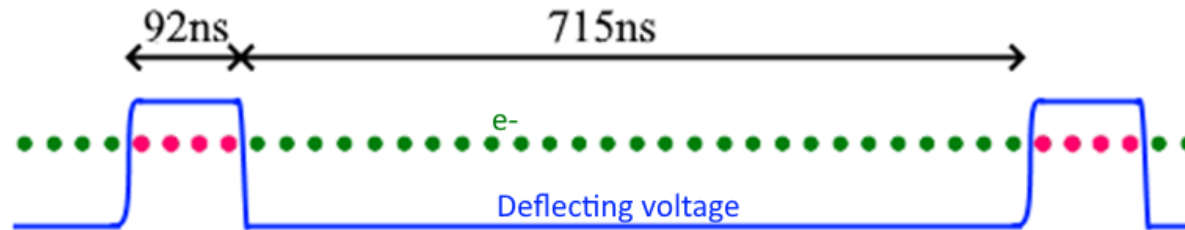
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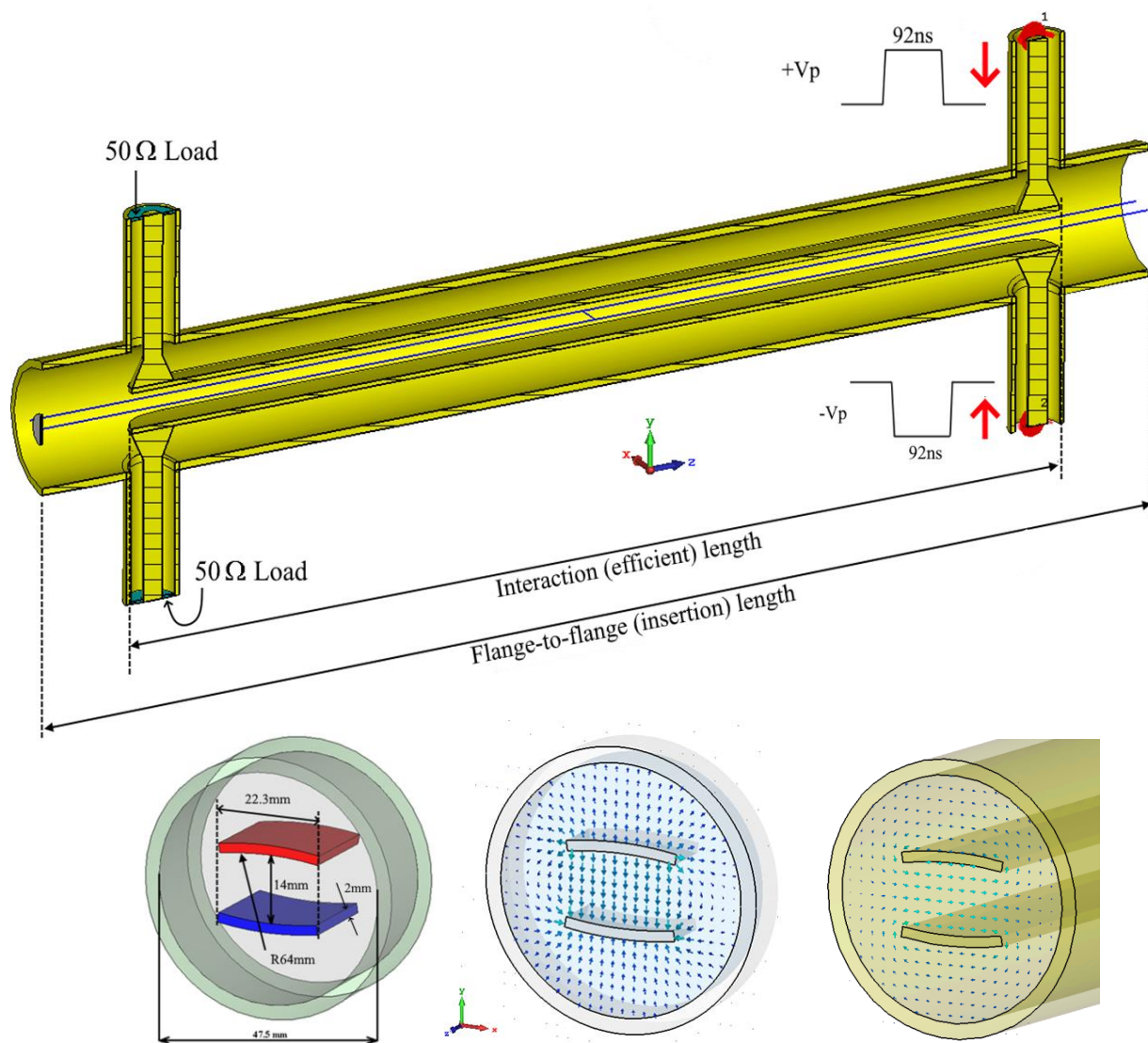
The ionization scattering of the electron beam with residual gas molecules causes ion trapping in the electron rings, both in the collider and electron cooling system. The trapped ions may cause emittance growth, tune shift, halo formation, and coherent coupled bunch instabilities. Therefore, the beam temporal structure needs gaps to clear the ions to prevent them from accumulating turn after turn. Typically, the gap in the bunch train has a length of a few percent of the ring circumference.

- A fast deflector (kicker) is needed for EIC ERL cooler to form a $\sim 100\text{ns}$ gap at $\sim 1\text{MHz}$ (37.5MHz, ultimately 98.5MHz micro-bunches)
- Aperture 14 mm
- Maximum insertion length is 75cm
- Stripline kicker is a practical solution for such need
- Radiabeam is building a kicker and two-channel pulsed power source intended to be installed and tested at Jefferson Lab

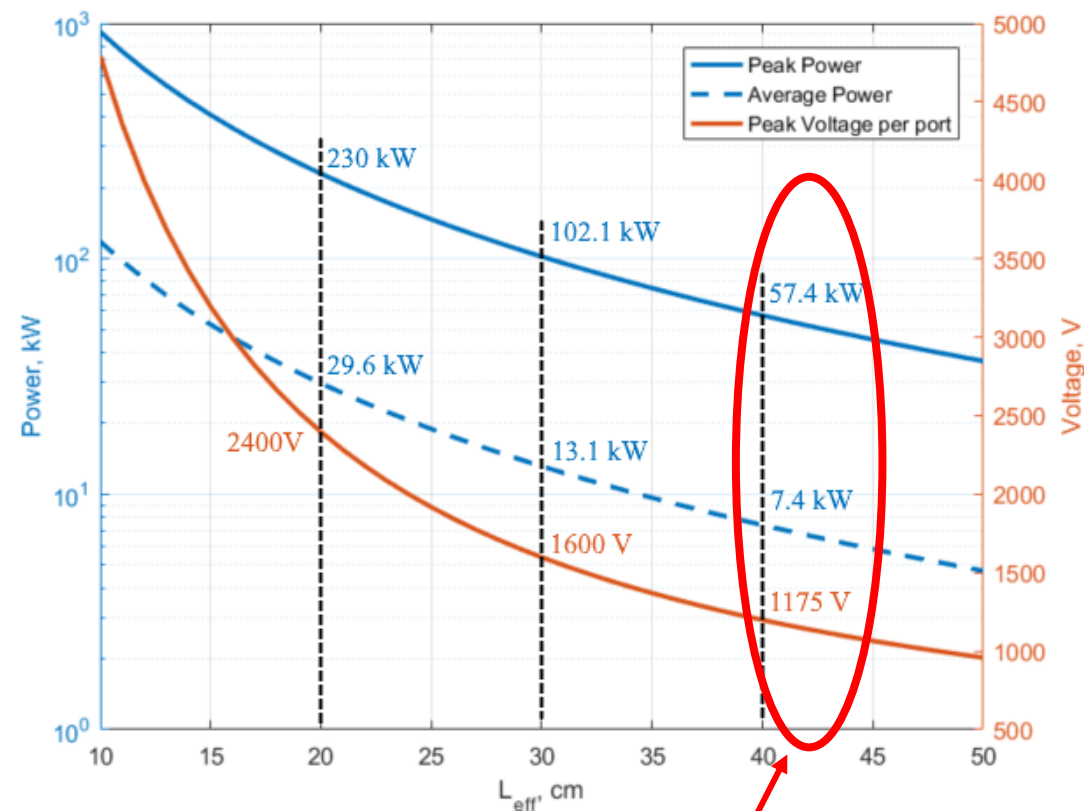




Parameter	Value
Deflecting angle	20 mrad (deflecting voltage 140 kV)
Flange-to-flange length	50 – 60 cm
Electron Beam Energy	7 MeV
Bunch Repetition Rate	37.5 MHz
Bunch rms transverse size	$\sigma=1$ mm
Deflecting Pulse Width	92 ns flat-top required to deflect 4 out of 31 bunches in train
Kicker operation per rate	1.4 MHz (715ns between the pulses)
Rise + Fall Time	<20 ns (10ns desired)
Aperture (gap)	14 mm
Required pulsed power	27.6 kW peak power per channel (55.2 kW total); 3.8 kW average power per channel (7.6 kW total)



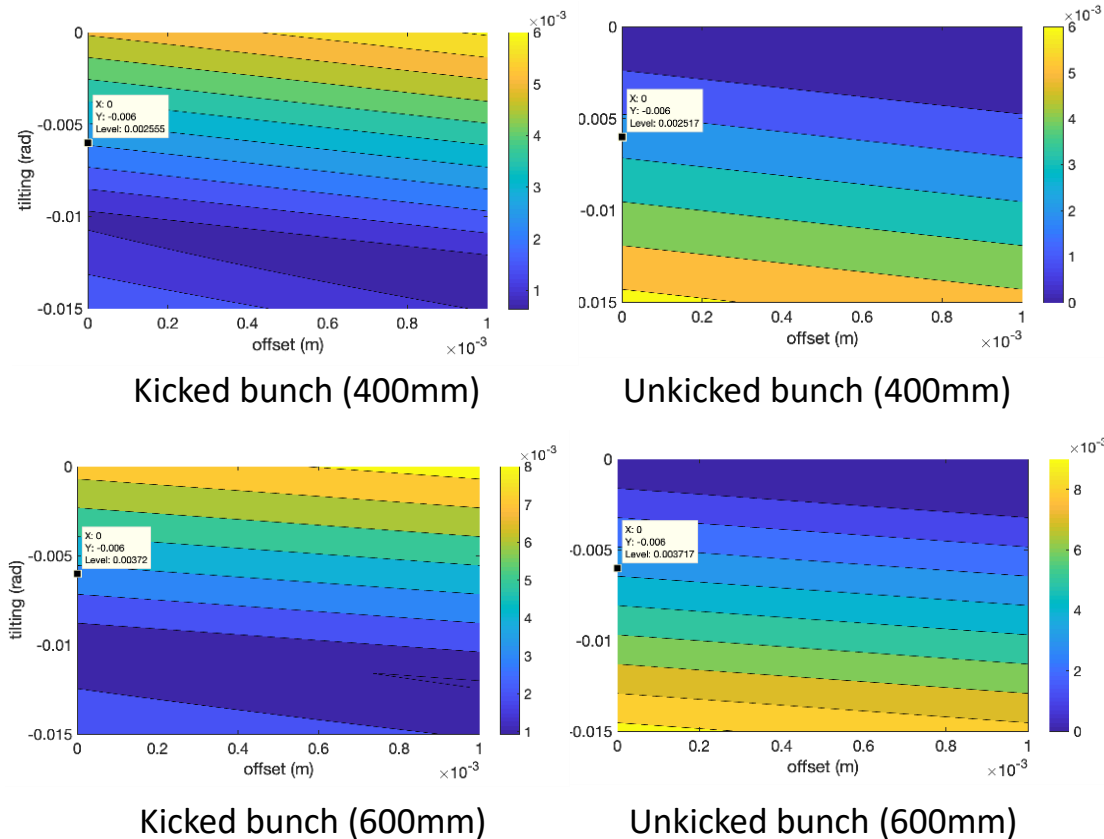
Power required for 20mrad deflection



40cm interaction length

Beam loss with various interaction lengths

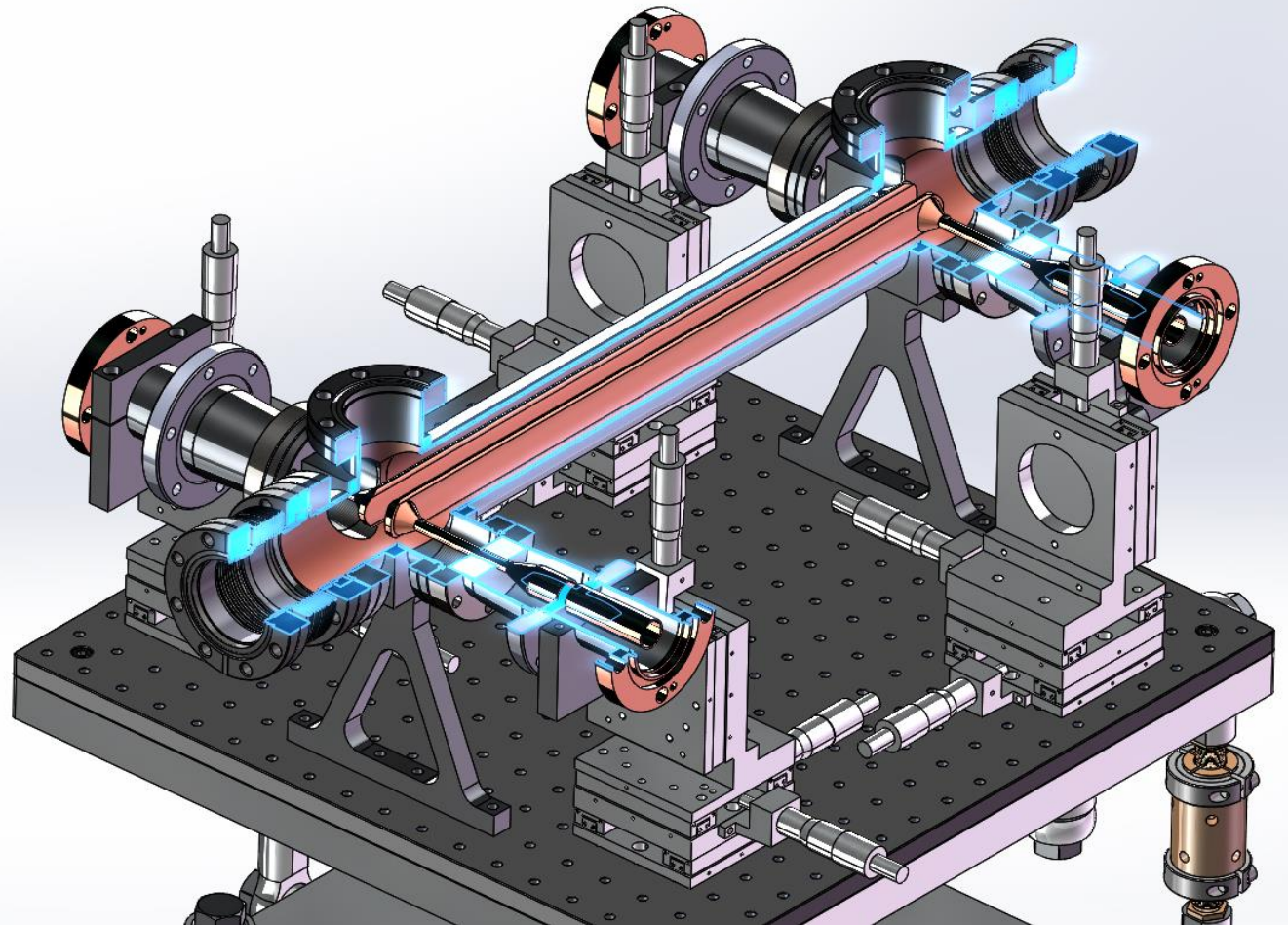
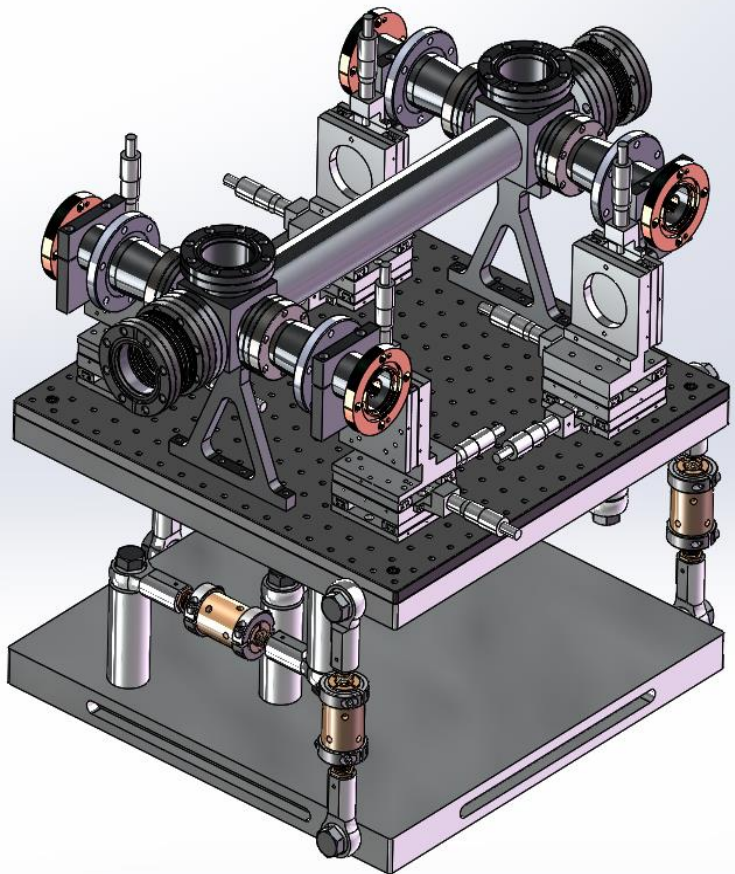
Exit offset spectrum over injection parameters



Analytic evaluation	Case 1	Case 2	Case 3	Case 4	Case 5	Case 6	Case 7	Case 8
20mrad Kick	yes	yes	yes	yes	yes	no	yes	no
L_{eff} (mm)	200	300	400	600	400	400	600	600
g (mm)	14	14	14	14	14	14	14	14
V_f (V)	2275	1560	1175	790	1175	1175	790	790
Offset _i (mm)	0	0	0	0	0	0	0	0
Tilt _i (mm)	0	0	0	0	-5	-5	-6	-6
Beam loss (%)	1×10^{-6}	8.8×10^{-5}	0.0027	0.21	5.4×10^{-5}	4.7×10^{-5}	1.6×10^{-3}	4.8×10^{-3}
P_b (W) LERF	4×10^{-4}	0.04	1.1	87.3	0.022	0.02	2	2
P_b (W) JLEIC	0.04	3.4	104.5	8.1×10^3	2.1	1.8	178	186
P_{RF} (kW)	14.5	6.8	3.85	1.75	3.85	3.85	1.75	1.75
CST simulation								
Beam loss (%)	7×10^{-6}	4×10^{-5}	1.6×10^{-3}	0.38	4.65×10^{-5}	4.66×10^{-5}	3.6×10^{-3}	3.6×10^{-3}
P_b (W) LERF	0.003	0.02	0.66	158	0.02	0.02	1.5	1.5
P_b (W) JLEIC	0.27	1.55	62	1.47×10^4	1.8	1.8	140	140
Space charge								
Beam loss (%)	-	-	-	-	1.8×10^{-3}	4.7×10^{-5}	-	-
P_b (W) LERF	-	-	-	-	0.7	0.02	-	-
P_b (W) JLEIC	-	-	-	-	70	1.8	-	-

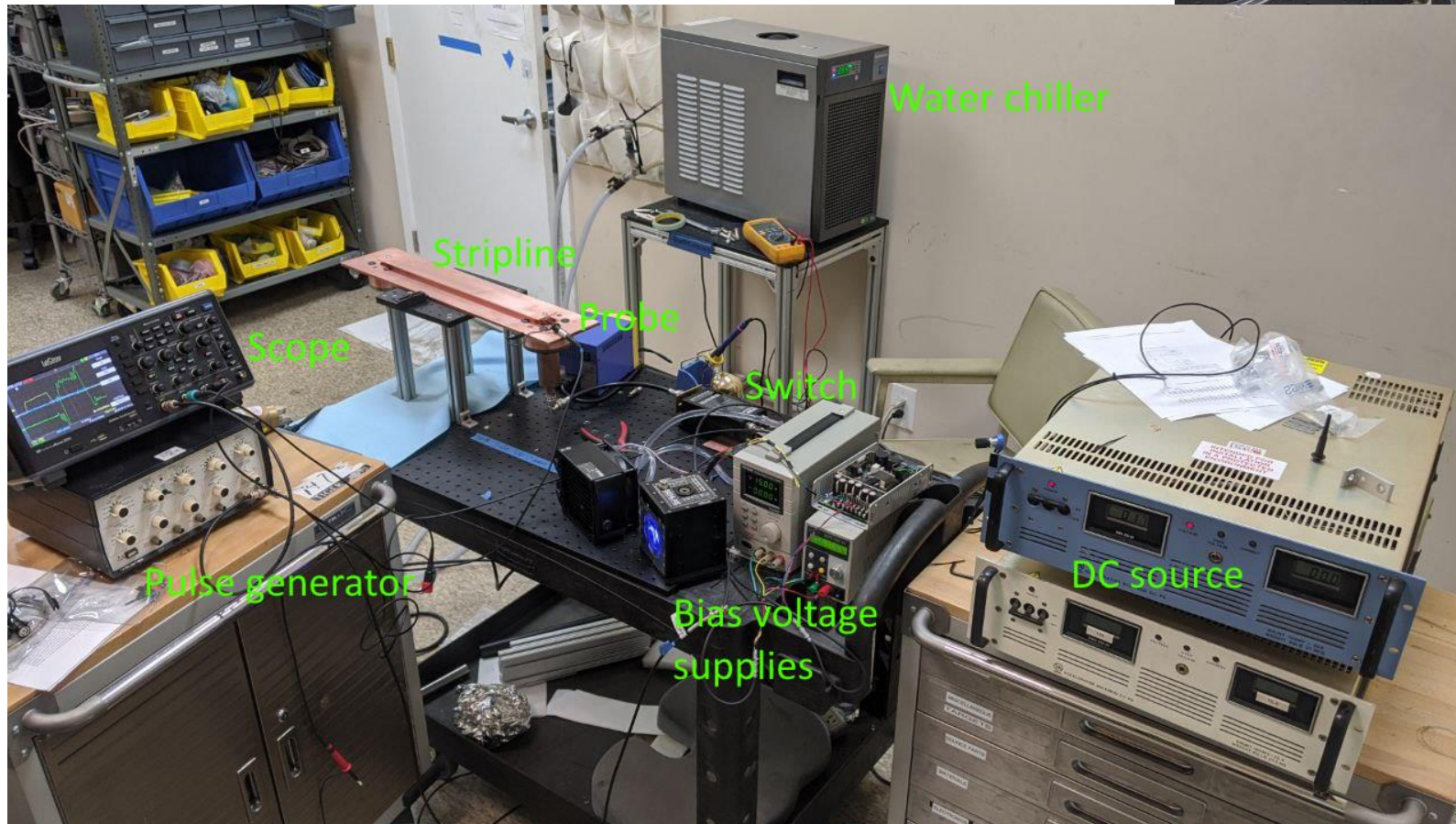
40cm interaction length

- Standard 1-5/8" EIA compatible
- XYZ Positioning stage



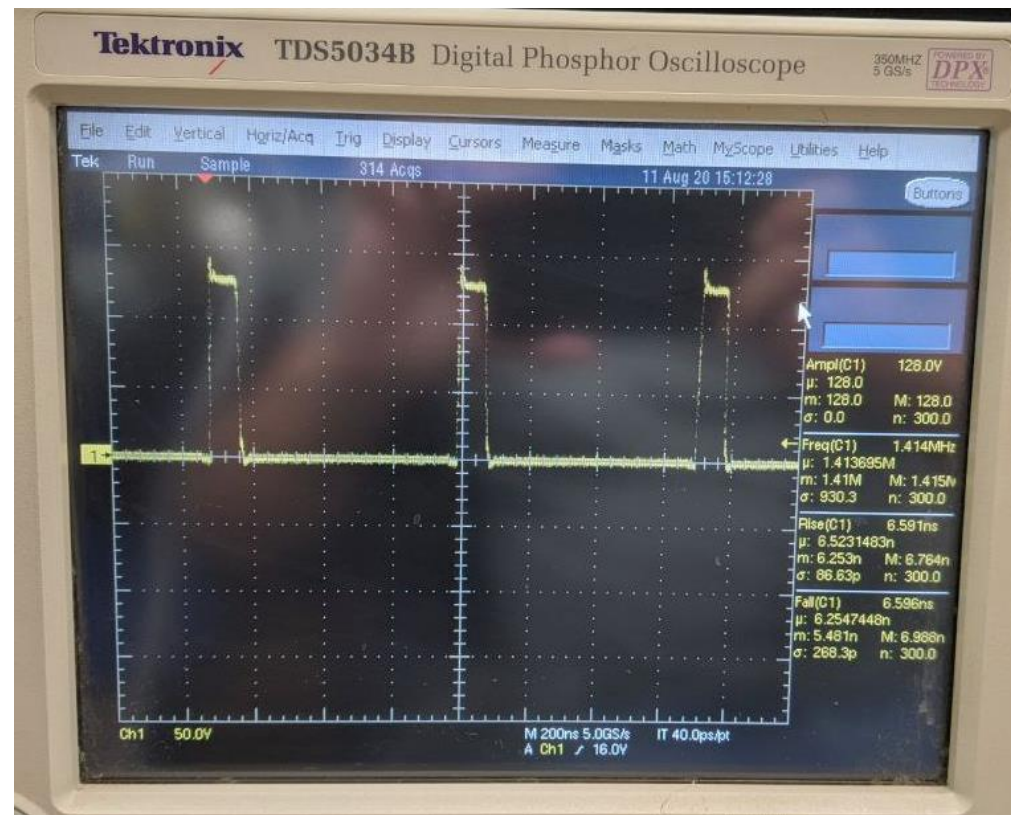
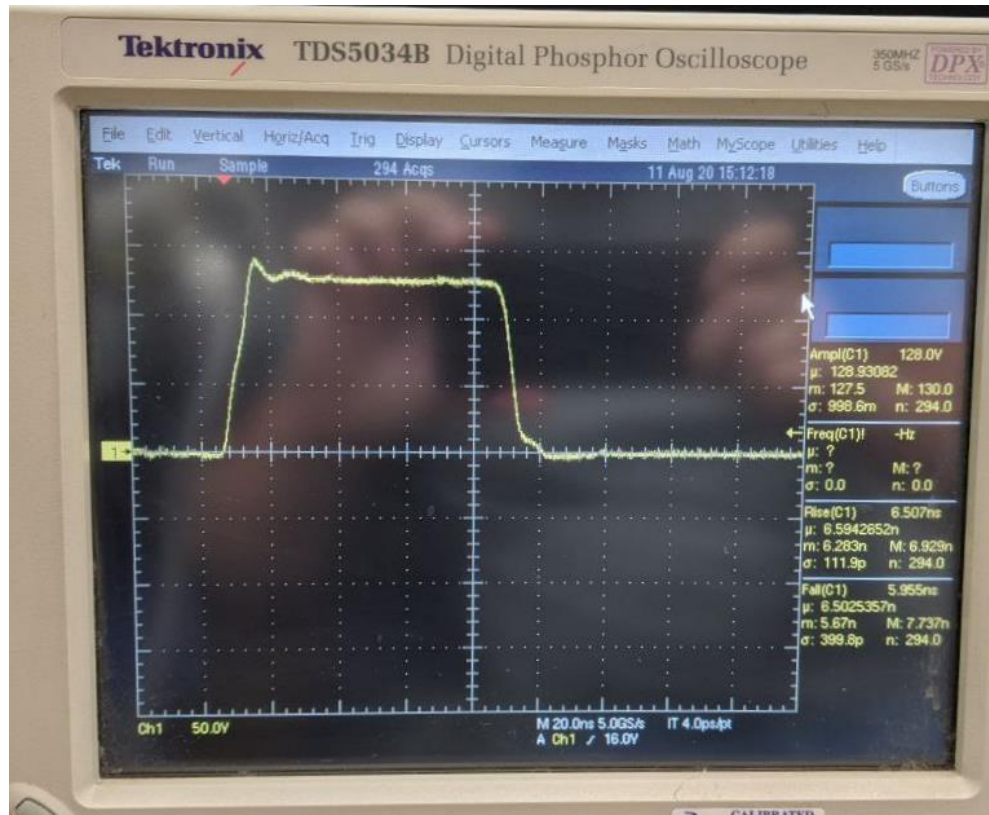
7 Pulser testing setup

- 50cm-long 50 Ohm stripline, VSWR <math>< 1.1</math> from DC to 1 GHz
- Si MOSFET and GaN water-cooled high-power switches
- 500 V / 10 A DC supply



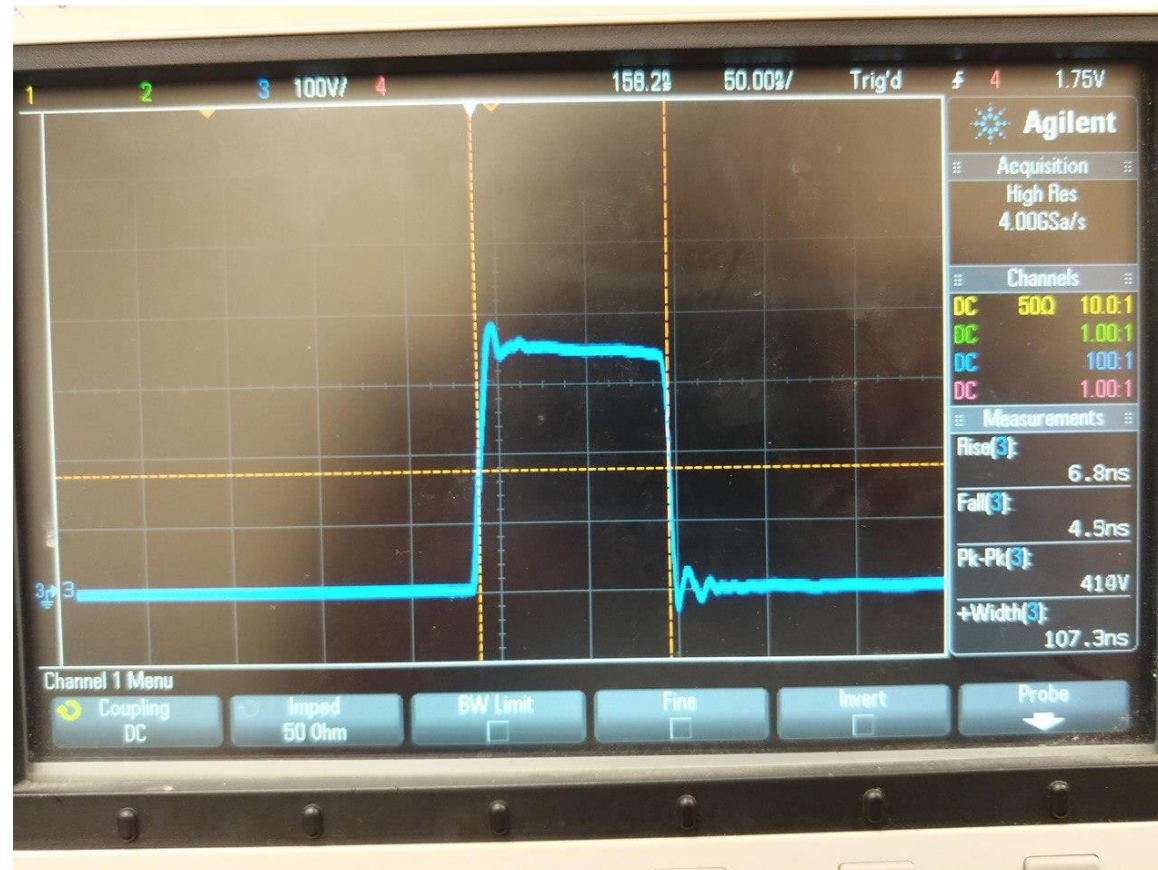
Achieved:

- 7ns rise and 6ns fall times at 100 ns flat-top with 87ps rms timing jitter
- Highly stable and controllable pulse length
- 1.4 MHz repetition rate
- **50% efficiency**



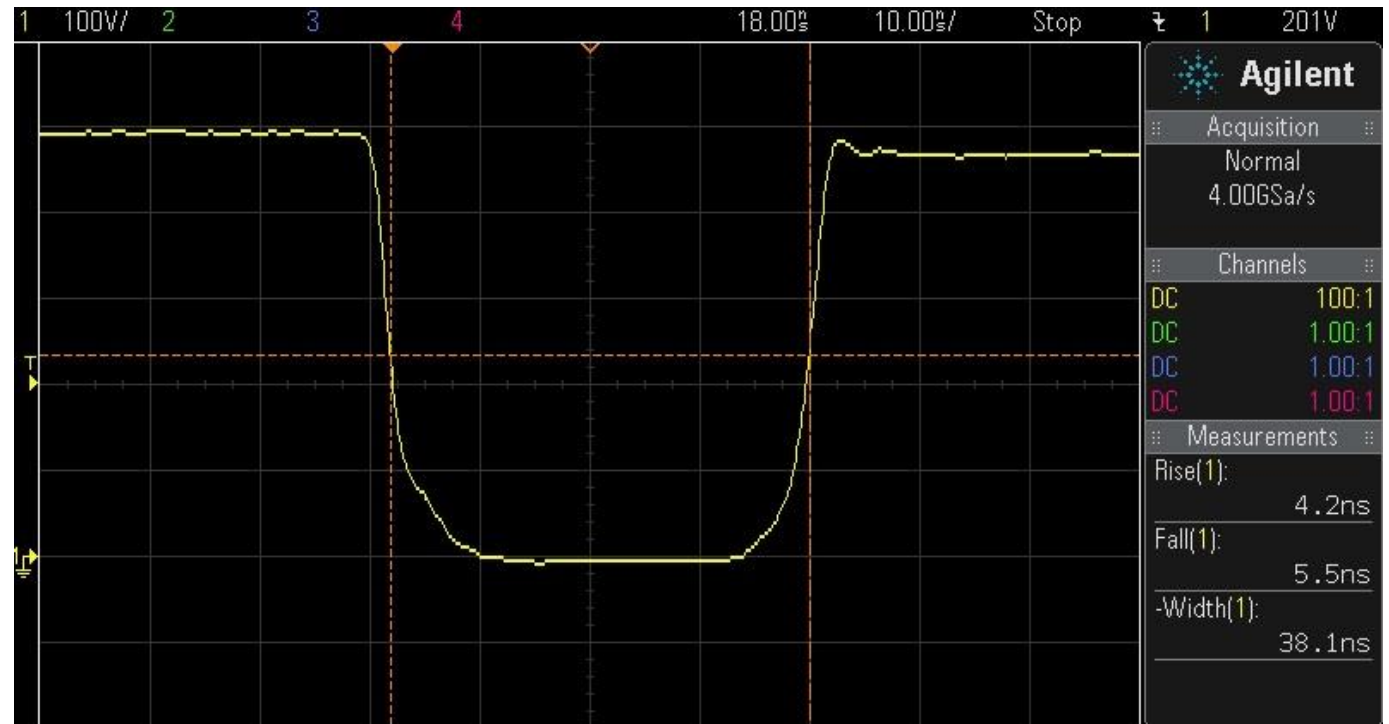
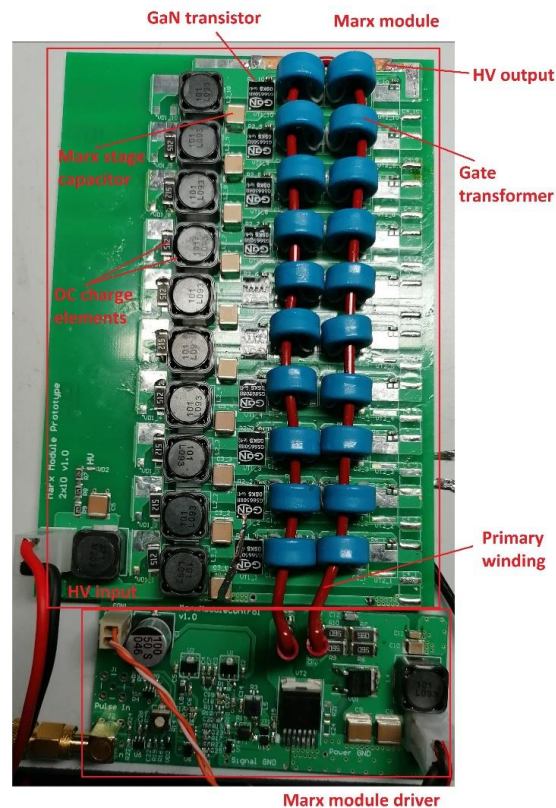
Achieved:

- 6.8ns rise and 4.5ns fall times @ 107 ns flat-top with 100ps rms timing jitter
- Highly stable and controllable pulse length
- 1.4 MHz repetition rate
- **82% efficiency**



Achieved*:

- 4.2 ns rise and 5.5ns fall times @ 38 ns flat-top
- 100 Hz repetition rate
- **95% efficiency**



*under Phase I project DE-SC0021548

- Tests with GaN at $\sim 1500\text{V}/30\text{A}$ to achieve $1175\text{V}/23.5\text{A}$ pulses
- Assemble two-channel pulser
- Finalize RF and thermal study of the kicker
- Kicker fabrication, assembly and tests
- Installation and beam-based tests at JLAB